

Hugues Vergnes

List of Publications by Year in descending order

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Version: 2024-02-01

13
papers

167
citations

1307594

7
h-index

1199594

12
g-index

13
all docs

13
docs citations

13
times ranked

192
citing authors

#	ARTICLE	IF	CITATIONS
1	Investigation of the initial deposition steps and the interfacial layer of Atomic Layer Deposited (ALD) Al ₂ O ₃ on Si. Applied Surface Science, 2019, 492, 245-254.	6.1	46
2	Detailed investigation of the surface mechanisms and their interplay with transport phenomena in alumina atomic layer deposition from TMA and water. Chemical Engineering Science, 2019, 195, 399-412.	3.8	35
3	Investigation of the densification mechanisms and corrosion resistance of amorphous silica films. Journal of Non-Crystalline Solids, 2019, 515, 34-41.	3.1	25
4	Local Kinetic Modeling of Aluminum Oxide Metal-Organic CVD From Aluminum Triisopropoxide. Chemical Vapor Deposition, 2011, 17, 181-185.	1.3	15
5	Development of a kinetic model for the moderate temperature chemical vapor deposition of SiO ₂ films from tetraethyl orthosilicate and oxygen. AIChE Journal, 2018, 64, 3958-3966.	3.6	9
6	Large temperature range model for the atmospheric pressure chemical vapor deposition of silicon dioxide films on thermosensitive substrates. Chemical Engineering Research and Design, 2020, 161, 146-158.	5.6	9
7	Tunable SiO ₂ to SiO _x C _y H films by ozone assisted chemical vapor deposition from tetraethylorthosilicate and hexamethyldisilazane mixtures. Surface and Coatings Technology, 2021, 407, 126762.	4.8	8
8	¹⁵ N in situ N ₂ -NH ₃ plasma pre-treatment of silicon substrate enhances the initial growth and restricts the substrate oxidation during alumina ALD. Journal of Applied Physics, 2019, 126, 125305.	2.5	6
9	Network hydration, ordering and composition interplay of chemical vapor deposited amorphous silica films from tetraethyl orthosilicate. Journal of Materials Research and Technology, 2021, 13, 534-547.	5.8	4
10	An innovative kinetic model allowing insight in the moderate temperature chemical vapor deposition of silicon oxynitride films from tris(dimethylsilyl)amine. Chemical Engineering Journal, 2022, 431, 133350.	12.7	4
11	An innovative GC-MS, NMR and ESR combined, gas-phase investigation during chemical vapor deposition of silicon oxynitrides films from tris(dimethylsilyl)amine. Physical Chemistry Chemical Physics, 2021, 23, 10560-10572.	2.8	3
12	Critical Level of Nitrogen Incorporation in Silicon Oxynitride Films: Transition of Structure and Properties, toward Enhanced Anticorrosion Performance. ACS Applied Electronic Materials, 0, , .	4.3	2
13	Beyond surface nanoindentation: Combining static and dynamic nanoindentation to assess intrinsic mechanical properties of chemical vapor deposition amorphous silicon oxide (SiO _x) and silicon oxycarbide (SiO _x C _y) thin films. Thin Solid Films, 2021, 735, 138844.	1.8	1